

# CVD-1000

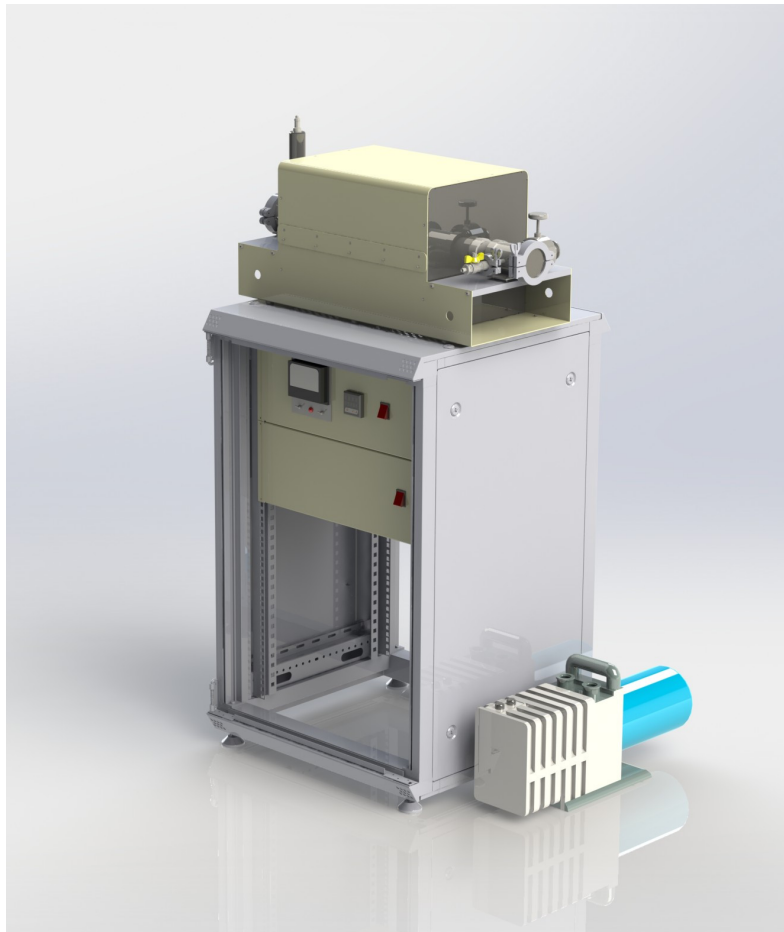
## Chemical Vapor Deposition System

### Technical specifications

Precision Quazar Tech Pvt. Ltd.

## Contents

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# 1 Furnace

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Parameter	Value
Geometry	Tubular
Maximum temperature	1100 °C
Power requirement	2000 Watt
<b>Tube specification</b>	
Material	Quartz
Diameter	ID: 45 mm, OD: 48 mm

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# 2 Temperature controller

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Parameter	Value
Maximum temperature	1100 °C
Power requirement	2000 Watt
Sensor	K-type thermocouple
Operation	Isothermal and ramp mode with PID control

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### 3 Vacuum system

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Parameter	Value
Pump type	Double stage rotary
Power requirement	500 Watt
Ultimate pressure	$10^{-3}$ mBar
Chamber isolation	Butterfly valve
Vacuum sensor	Pirani gauge

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### 4 Gas flow

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Parameter	Value
Channels	4
Controller	Rotameter type
Maximum flow	1 liter/min per channel

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